## WHAT IS CLAIMED IS:

- 1. A beam inspection apparatus, comprising:
  - a beam source that discharges a beam;
- a stage system that holds a specimen and moves continuously in at least one direction;
  - a primary optical system that directs the beam to the specimen;
- a secondary optical system that guides a secondary beam coming from the specimen;
- a sensor that outputs an electric signal of the specimen image from the secondary beam;
- an image processor that generates image information of the specimen by processing the electric signal output by the sensor; and
- a host computer that generates an inspection timing signal for controlling the sensor to transfer the image information at a preset data transfer rate,

wherein the stage system is moved at a speed in conformity to the inspection timing signal, and a signal charge of the specimen image converted by the sensor is transferred at an effective data transfer rate of larger than 2.29 x 10<sup>7</sup> Hz/pix and at a line rate of larger than 11175Hz/line.

- 2. The beam inspection apparatus of claim 1, wherein the primary optical system shapes the beam into an elliptical form.
- 3. The beam inspection apparatus of claim 1, wherein the primary optical system shapes the beam into a rectangular form.
- 4. The beam inspection apparatus of claim 1, further comprising a numerical aperture having an opening section arranged to become a focus position of a first lens from the specimen.
  - 5. A beam inspection apparatus for inspecting a specimen comprising:
    - a beam source that discharges a beam;
    - a primary optical system that directs the beam to the specimen;
- a secondary optical system that guides a secondary beam coming from the specimen;
- a sensor that outputs an electric signal of the specimen image from the secondary beam;

an image processor that generates image information of the specimen by processing the electric signal output by the sensor;

a stage system that holds the specimen and moves in at least one direction, the stage system having a laser interferometer for reading an x·y position of the stage and a stage controller that drives the stage,

wherein the image information of the specimen generated by the image processor is compensated with regard to a specimen image displacement arising from a speed variation or a mechanical vibration of the stage system.

- 6. The beam inspection apparatus of claim 5, further comprising a numerical aperture having an opening section arranged to become a focus position of a first lens from the specimen.
- 7. The beam inspection apparatus of claim 5, wherein the beam is applied perpendicularly to a surface of the specimen.
  - 8. An electron beam inspection apparatus for inspecting a specimen, comprising: an electron beam source that discharges an electron beam; a primary optical system that directs the electron beam to the specimen:
- a sensor that outputs an electric signal of specimen information from a secondary beam;

an information processor that generates information of the specimen by processing the electric signal output by the sensor;

a stage system that holds the specimen and moves in at least one direction, the stage system having a laser interferometer that reads an x·y position of the stage and a stage controller that drives the stage,

wherein the information of the specimen generated by the processor is compensated with regard to a specimen information displacement arising from a speed variation or a mechanical vibration of the stage system.

- 9. The electron beam inspection apparatus of claim 8, further comprising a secondary optical system that guides a secondary beam coming from the specimen.
  - 10. A beam inspection apparatus, comprising:
    - a beam source that discharges a beam;
- a stage system that holds a specimen and moves continuously in at least one direction;
  - a primary optical system that directs the beam to the specimen;

a secondary optical system that guides a secondary beam coming from the specimen;

a sensor that outputs an electric signal of the specimen image from the secondary beam;

an image processor that generates image information of the specimen by processing the electric signal output by the sensor; and

a host computer that generates an inspection timing signal for controlling the sensor to transfer the image information at a preset data transfer rate,

wherein the stage system is moved at a speed in conformity to the inspection timing signal.